

0756-575

07/702,492

INFORMATION DISCLOSURE CITATION 29 1992

(Use several sheets if necessary)

APPLICANT

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FILING DATE

May 20, 1991

GROUP

Art Unit 1104

U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

[illegible]

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

GAG		Japanese Journal of Applied Physics, Vol. 23, No. 10, October 1984, Kamisako et al.: ANALYSIS OF DEPOSITION RATE DISTRIBUTION IN THE PHOTO-CVD OF a-Si
		BY A UNIFIED REACTOR WITH A LAMP, pp. L776-L778..

EXAMINER

George Gondreau

DATE CONSIDERED

8-9.3

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.